

# CO<sub>2</sub>-PROCESSES PHOTORESISTS, POLYMERS, AND PHOTOACTIVE COMPOUNDS FOR MICROLITHOGRAPHY

## Abstract of the Disclosure

- 5 A process of forming a resist image in a microelectronic substrate comprises the steps of contacting the substrate with a composition first comprising carbon dioxide and a component selected from the group consisting of at least one polymeric precursor, at least one monomer, at least one polymeric material, and mixtures thereof to deposit the component on the
- 10 substrate and form a coating thereon; then imagewise exposing the coating to radiation such that exposed and unexposed coating portions are formed; then subjecting the coating to a second composition comprising carbon dioxide having such that either one of the exposed or the unexposed coating portions are removed from the substrate and the other coating portion is developed
- 15 and remains on the coating to form an image thereon.